

Thin Film Deposition With The Sputtering Lab @ LIN

Tuesday, 29 October 2019 14:00 (30 minutes)

Thin film deposition is a technique useful in many scientific domains.

Our sputtering lab provides their coating services for all PSI groups, developing novel thin layers, lending support in sample preparation and manufacturing of instrument components.

The lab is equipped with 2 sputtering plants that have 3 target stations each and cover 50x200 mm² and 400 x 580 mm² respectively. Both DC magnetron and HF-sputtering are possible, including reactive sputtering.

We specialize in multilayer and supermirror deposition for neutron optical applications. Recent successes include m=6 Ni-Ti supermirrors and 10B coatings.

We would like to push the development of supermirrors further and would benefit from additional expertise in thin layer characterization.

Position

Scientist

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